

UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspio.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/660,561	09/12/2003	Jeong-Wook Lee	030681-572	5312
21839 BUCHANAN.	7590 05/14/2007 INGERSOLL & ROONE	EXAMINER		
POST OFFICE	EBOX 1404	MULPURI, SAVITRI		
ALEXANDRIA, VA 22313-1404			ART UNIT	PAPER NUMBER
			2812	
			MAIL DATE	DELIVERY MODE
			05/14/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Advisory Action Before the Filing of an Appeal Brief

Application No.	Applicant(s)		
10/660,561	LEE ET AL.		
Examiner	Art Unit		
Savitri Mulpuri	2812		

• • • • • • • • • • • • • • • • • • • •	Examinion	Artonic					
	Savitri Mulpuri	2812					
The MAILING DATE of this communication appe	ears on the cover sheet with the	correspondence add	ress				
THE REPLY FILED FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE.							
. Mathematical The reply was filed after a final rejection, but prior to or on the same day as filing a Notice of Appeal. To avoid abandonment of this application, applicant must timely file one of the following replies: (1) an amendment, affidavit, or other evidence, which places the application in condition for allowance; (2) a Notice of Appeal (with appeal fee) in compliance with 37 CFR 41.31; or (3) a Request for Continued Examination (RCE) in compliance with 37 CFR 1.114. The reply must be filed within one of the following							
time periods:							
 a)							
no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection.							
Examiner Note: If box 1 is checked, check either box (a) or (b). ONLY CHECK BOX (b) WHEN THE FIRST REPLY WAS FILED WITHIN							
TWO MONTHS OF THE FINAL REJECTION. See MPEP 7 Extensions of time may be obtained under 37 CFR 1 136(a). The date		136/a) and the appropria	te extension fee				
Extensions of time may be obtained under 37 CFR 1.136(a). The date on which the petition under 37 CFR 1.136(a) and the appropriate extension fee have been filed is the date for purposes of determining the period of extension and the corresponding amount of the fee. The appropriate extension fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened statutory period for reply originally set in the final Office action; or (2) as set forth in (b) above, if checked. Any reply received by the Office later than three months after the mailing date of the final rejection, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).							
NOTICE OF APPEAL 2. The Notice of Appeal was filed on A brief in com-	oliopoo with 27 CER 41 27 must be	filed within two month	as of the data of				
2. The Notice of Appeal was filed on A brief in compliance with 37 CFR 41.37 must be filed within two months of the date of filing the Notice of Appeal (37 CFR 41.37(a)), or any extension thereof (37 CFR 41.37(e)), to avoid dismissal of the appeal. Since a Notice of Appeal has been filed, any reply must be filed within the time period set forth in 37 CFR 41.37(a).							
AMENDMENTS	but animate the date of filling a bridge	6					
3. The proposed amendment(s) filed after a final rejection,			ecause				
 (a) ☐ They raise new issues that would require further consideration and/or search (see NOTE below); (b) ☐ They raise the issue of new matter (see NOTE below); 							
(c) They are not deemed to place the application in be appeal; and/or	• •	educing or simplifying	the issues for				
(d) ☐ They present additional claims without canceling a	corresponding number of finally re	jected claims.					
NOTE: (See 37 CFR 1.116 and 41.33(a)).			•				
4. The amendments are not in compliance with 37 CFR 1.121. See attached Notice of Non-Compliant Amendment (PTOL-324).							
5. Applicant's reply has overcome the following rejection(s):							
 Newly proposed or amended claim(s) would be a non-allowable claim(s). 		•					
7. For purposes of appeal, the proposed amendment(s): a) how the new or amended claims would be rejected is pro The status of the claim(s) is (or will be) as follows:		ill be entered and an e	explanation of				
Claim(s) allowed:							
Claim(s) objected to:	•						
Claim(s) rejected:							
Claim(s) withdrawn from consideration: AFFIDAVIT OR OTHER EVIDENCE							
8. ☐ The affidavit or other evidence filed after a final action, but	ut before or on the date of filing a N	lotice of Appeal will no	ot be entered				
because applicant failed to provide a showing of good an was not earlier presented. See 37 CFR 1.116(e).							
9. The affidavit or other evidence filed after the date of filing entered because the affidavit or other evidence failed to showing a good and sufficient reasons why it is necessar	overcome <u>all</u> rejections under appe	eal and/or appellant fa	ils to provide a				
10. ☐ The affidavit or other evidence is entered. An explanation REQUEST FOR RECONSIDERATION/OTHER			·				
 The request for reconsideration has been considered by See Continuation Sheet. 	ut does NOT place the application	in condition for allowa	nce because:				
12. ☐ Note the attached Information Disclosure Statement(s), (PTO/SB/08) Paper No(s).							
13.		5 ·a	whi				
		Savitri Mulpuri					
		Primary Examiner					

Continuation of 11. does NOT place the application in condition for allowance because: Applicant argues that Tsakalakos does not teach sequentially growing semiconductor layer, mask layer and metal layer and regrowing the semiconductor layer completely fill the nanoholes in the mask and extend above the mask to cover the mask layer. However, Tsakalakos teaches all the limitations except forming metal layer. Zhang teaches metal layer and etching metal layer by anodization to form nanoholes in the mask and removing the anodized metal layer. It would have been obvious to one of ordianry skill in the art to form nanoholes in the mask in the invention of Tsakalakos by using metal layer followed by anodization instead of forming and etching block copolymer layer to form nanoholes, which eventaully aid to form nanoholes in the mask. The goal in both Tsakalakos and Zhang is to form mask with nanoholes and both chose different methods to form nanoaholes, which are analogus. However, in both references the final structure is the substrate covered with mask having nanoholes. In other words copolymer layer in Tsakalakos and metal layer in Zhang are eventually removed once nano holes are formed within the underlying mask layer and then finally regrow the semiconductor layer in the nanoholesand above the mask.